

AMENDMENTS TO THE CLAIMS

Please amend the claims as follows:

1. - 3. (Canceled).
4. (Previously Presented) The vacuum deposition apparatus according to claim 18, wherein the susceptor is made of a quartz material.
5. (Previously Presented) The vacuum deposition apparatus according to claim 18, wherein the groove has a polygonal configuration.
6. (Previously Presented) The vacuum deposition apparatus according to claim 18, wherein a bottom face of the groove has a curved configuration.
7. (Previously Presented) The vacuum deposition apparatus according to claim 18, wherein a bottom face of the groove includes an incline plane and a perpendicular plane.
8. (Previously Presented) The vacuum deposition apparatus according to claim 18, wherein the groove has a V-shaped configuration.
9. (Canceled)

10. (Previously Presented) The vacuum deposition apparatus according to claim 4, wherein the susceptor is in direct contact with the glass substrate when the glass substrate is heated.

11. – 15. (Canceled)

16. (Previously Presented) The vacuum deposition apparatus according to claim 18, wherein the susceptor is rectangular.

17. (Canceled)

18. (Currently Amended) A vacuum deposition apparatus having a process chamber, comprising:

a susceptor having a recessed central portion provided with lift pins and raised perimeter portions for heating a glass or quartz substrate, all four edges each raised perimeter portion of the susceptor acting as a sliding portion on which to slide the glass or quartz substrate toward a stopped position by stopping pins placed on the sliding portion, ~~the susceptor having a raised perimeter portion structured to accommodate sliding of the glass substrate~~ without incurring contact of the glass or quartz substrate with a build up of vacuum deposited material on the raised perimeter ~~portion~~ portions of the susceptor;

means for positioning the glass or quartz substrate into contact with the susceptor at a non-parallel angle to a top surface of the susceptor and for permitting edges of the glass or quartz

substrate to slide along a raised perimeter portion of the susceptor toward stopping pins until the glass or quartz substrate is substantially parallel with the susceptor;

wherein ~~the each raised perimeter portion of the~~ susceptor includes a groove ~~formed in all four edges of said raised perimeter portion~~ at a location of the stopping pins to receive vacuum deposited material and thereby minimize formation by the vacuum deposited material of a film on the raised perimeter portion of the susceptor, and

wherein a length of said raised perimeter portion, measured from a stopper pin to a contact position of the glass or quartz substrate on the top surface of the susceptor ~~said groove, to the recessed center portion of the susceptor~~ is about 10 mm to stabilize transfer ~~minimize breakage of the glass or quartz substrate by preventing a severe bend of the glass or quartz substrate during transfer of the glass or quartz substrate to the susceptor.~~

19. (New) A method of stabilizing transfer of a glass or quartz substrate to a susceptor for heating the glass or quartz substrate,

wherein edge portions of the susceptor are adapted to permit sliding of the glass or quartz substrate to a stopped position by stopping pins placed on the edge portions, the susceptor having a raised perimeter portion structured to accommodate sliding of the glass substrate without incurring contact of the glass or quartz substrate with a build up of vacuum deposited material on the raised perimeter portion of the susceptor;

wherein the vacuum deposition apparatus includes a means for positioning the glass or quartz substrate into contact with the susceptor at a non-parallel angle to a top surface of the susceptor and for permitting edges of the glass or quartz substrate to slide along a portion of the

susceptor toward stopping pins until the glass or quartz substrate is substantially parallel with the susceptor,

wherein the susceptor includes a groove formed in all four edges of said raised perimeter portion at a location of the stopping pins to receive vacuum deposited material and thereby minimize formation by the vacuum deposited material of a film on the raised perimeter portion of the susceptor, the method comprising:

making a length of said raised perimeter portion, measured from a stopper pin to a contact position of the glass or quartz substrate on the top surface of the susceptor to be about 10mm to stabilize the transfer of the glass or quartz substrate to the susceptor.